

SHIGA7.004APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	: Maruyama et al.
Appl. No.	: 10/522,036
Filed	: January 19, 2005
For	: CHEMICAL AMPLIFICATION TYPE POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN FORMING METHOD
Examiner	: Lee, Sin J
Group Art Unit	: 1752

AMENDMENT AND RESPONSE TO ADVISORY ACTION AND FINAL OFFICE ACTION

Mail Stop AF

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Advisory Action mailed **December 26, 2006**, and the Office Action mailed **September 15, 2006**, please consider the following amendments and remarks.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 13 of this paper.

Please
Enter
S.J.L.
1-26-07